SPIE. ADVANCED LITHOGRAPHY

San Jose, California

Join Us!

Advances in Patterning Material and Processes

February 27, 2019

Poster Session: Filtration (PS3) | Convention Center, Hall 2

Time	Presentation
5:30 p.m. – 7:30 p.m.	Filter technology developments to address defectivity in leading-edge photoresists Tetsu Kohyama, Fumiya Kaneko, Kozue Miura, Nihon — Entegris, K. K. (Japan) Alketa Gjoka, Jad Jaber — Entegris, Inc. (USA)
	A new tailored point-of-use filter to reduce immersion lithography downtime and defects Aiwen Wu, Annie Xia — Entegris, Inc. (USA) Hareen Bayana — Entegris, GmbH (Germany)
	An exploration of the use of fluoropolymers in photofiltration Aiwen Wu, Annie Xia — Entegris, Inc. (USA)
	Bridging the defect gap in EUV photoresist Tetsu Kohyama, Fumiya Kaneko, Nihon — Entegris, K. K. (Japan) Alketa Gjoka, Jad Jaber — Entegris, Inc. (USA)

February 28, 2019

Session 11: Material Supplier | Convention Center, Grand Ballroom 220C

Time	Presentation
8:00 a.m. – 10:00 a.m.	Expanding the lithographer's toolkit to reduce variability: Filtration considerations Jennifer Braggin, Vinay Goel, Aiwen Wu — Entegris, Inc. (USA)

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